Recent Advances in Artificial Intelligence and Their Engineering Application

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Message from the Guest Editor

Dear Colleagues,

In recent years, artificial intelligence (AI) has seen an unprecedented surge of interest in the engineering field thanks to significant technological advances that extend the capabilities of computers and increase their performance for development, improving sustainability, the efficiency of industrial systems, process integration and intensification. These advances open vast prospects for technological innovation and automation in work situations in the various fields of engineering.

This Special Issue is devoted to the latest and future theoretical innovations of AI and their applications in industrial domains. In this Special Issue, we also invite case studies, comprehensive reviews, and investigative articles to provide a valuable reference for researchers and practitioners on the challenges, opportunities, and future development of AI in engineering.

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Special Issue

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Message from the Editor-in-Chief

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